CLAIMS

1. A sputtering target for a heat-assisted magnetic recording medium, consisting of an FePt alloy, a nonmagnetic material, and incidental impurities, wherein the nonmagnetic material is an oxide having a melting point of 800°C or higher and 1100°C or lower.

2. The sputtering target for a heat-assisted magnetic recording medium according to Claim 1, wherein the FePt-alloy further comprises one or more elements selected from Ag, Au, and Cu.

3. The sputtering target for a heat-assisted magnetic recording medium according to Claim 1 or 2, wherein the nonmagnetic material is one or more oxides selected from SnO, PbO, and Bi_2O_3.

4. The sputtering target for a heat-assisted magnetic recording medium according to any one of Claims 1 to 3, comprising, relative to the sputtering target for a heat-assisted magnetic recording medium, 25 vol% or more and 40 vol% or less of the nonmagnetic material.